HEWLETT-PACKARD COMPANY Intellectual Property Administration O. Box 272400 Collins, Colorado 80527-2400

PATENT APPLICATION

ATTORNEY DOCKET NO. 100201346-5

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

10/668,558

ventor(s):

James Stasiak et al

Confirmation No.:

Application No.: Unassigned

Examiner: Rao, Shrinivas H

Filing Date:

Sep 22, 2003

Group Art Unit: 2814

Title:

Nanometer-Scale Semiconductor Devices And Method Of Making

Commissioner for Patents PO Box 1450 Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

Sir:

This Information Disclosure Statement is submitted:

(x)	under 37 CFR 1.97(b), or (Within three months of filing national application; or date of entry of national application; or before mailing date of first office action on the merits; whichever occurs last)
()	under 37 CFR 1.97 (c) together with either a: () Statement under 37 CFR 1.97(e), or () a \$180.00 fee under 37 CFR 1.17(p), or (After the CFR 1.97 (b) time period, but before final action or notice of allowance, whichever occurs first)
()	under 37 CFR 1.97 (d) together with a: () Statement under 37 CFR 1.97(e)(1) or (2), and () a \$180.00 fee set forth in 37 CFR 1.17(p). (Filed after final action, a notice of allowance, on or before payment of the issue fee)

Please charge to Deposit Account 08-2025 the sum of \$0.00 . At any time during the pendency of this application, please charge any fees required or credit any overpayment to Deposit Account 08-2025 pursuant to 37 CFR 1.25.

- Applicant(s) submit herewith Form PTO 1449 Information Disclosure Citation together with copies, of patents, publications or other information of which applicant(s) are aware, which applicant(s) believe(s) may be material to the examination of this application and for which there may be a duty to disclose in accordance with 37 CFR 1.56.
- A concise explanation of the relevance of foreign language patents, foreign language publications and other foreign language information listed on PTO Form 1449, as presently understood by the individuals(s) designated in 37 CFR 1.56 (c) most knowledgeable about the content is given on the attached sheet, or where a foreign language patent is cited in a search report or other action by a foreign patent office in a counterpart foreign application, an English language version of the search report or action which indicates the degree of relevance found by the foreign office is listed on form PTO 1449 and is enclosed herewith.

It is requested that the information disclosed herein be made of record in this application.

(X)	I hereby certify that this correspondence deposited with the United States Postal as first class mail in an envelope address Commissioner for Patents, Alexandria, V 22313-1450. Date of Deposit: _ 9/24	Service ed to: A
	OR	•
()	I hereby certify that this paper is being transmitted to the Patent and Trademark facsimile number	Office on

Typed Name: Donald J. Coulman

Respectfully submitted,

James Stasiak et al

Donald J. Coulman

Atterney/Agent for Applicant(s)

Reg. No. 50.406

Date: 9/24/2003

Telephone No.: (541) 715-1694

Rev 05/03 (IDSCERT)

PATENT APPLICATION

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LIST OF PATENTS AND PUBLICATIONS FOR APPLICANT'S INFORMATION DISCLOSURE STATEMENT

(Use several sheets if necessary)

100201346-5 APPLICANT

Jam s Stasiak, et al

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APPLICATION NO. CONFIRMATION NO.

Sept 22, 2003

GROUP 2814

DECEDEN	ICE	DESIGN	IATION!

U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	PUBLICATION DATE	NAME	Pages, Columns, Lines Where Relevant Passages or Figures Appear
	1A				
	1B				
	1C	:			
	1D				
	1E				
	1F				
	1G				
	1H				
	11				
	1J				
	1K				

FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	PUBLICATION DATE	NAME OF PATENTEE OR APPLICANT	Pages/Columns/Lines Where Relevant Passages/Figures Appear	Check if Translation attached
1L					
1N					
1N					
10	1				
1P					

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, etc.)

	1Q	Otto-M et al. "Characterization and applicati Engineering (Netherlands), vol 57-58, pages	ion of a UV-based imprint techinque" Microelectronic 361-6, September 2001.	
	1R	Beck-M et al., "Improving nanoimprint Lithography stamps for 10nm features", Proceedings of the 2001 1st IEEE Conference on Nanotechnology, IEE-Nano 2001, pages 17-22, 2001.		
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EXAMINER			DATE CONSIDERED	